

Method for Forming Rough Surface

ABSTRACT OF THE INVENTION

5 A method for forming rough surface: first, provide a substrate; then, immerse a surface layer of substrate in a solution which is able to etch surface layer; next, form numerous bubbles in solution such that part of bubbles are located on a surface of surface layer, where surface is contacted with solution; finally, remove solution. The method also could
10 form bubbles in solution before surface layer is immersed in solution, and could perform a dry process after solution is removed. Significantly, this method at least could be used to enhance adhesion of photoresist and increases capacitance of capacitor.